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Gottlieb Oehrlein is a scientist and engineer who is best known for his work on the use of non-equilibrium plasma for advanced materials processing, in particular for his contributions to the understanding/control of plasma-surface interactions (PSI) and advancement of plasma etching methods. He was borne in Germany and received a Vordiplom in Physics from Würzburg University, Germany (1976), and a Ph.D. in Physics from the State University of New York (SUNY), Albany (1981). Subsequently, he joined IBM's Research Division, Yorktown Heights as a Research Staff Member and performed research in Plasma Science and Technology. In 1993 he returned as a Professor of Physics to State University of New York, Albany, and in 2000 joined Department of Materials Science and Engineering and Institute for Research in Electronics and Applied Physics at University of Maryland, College Park. His work has been recognized by several awards, including the Electrochemical Society's Electronics and Photonics Division Award, the John Thornton Memorial Award of AVS, the DPS Nishizawa Award, and the Plasma Materials Hall of Fame award of the Japan Society for the Promotion of Science.